

	Type	L #	Hits	Search Text	DBs	Time Stamp	C o m m e n t s	E r r o r s	E r r o r s
1	BRS	L1	13417	(slurry or cmp or "chemical mechanical polishing") and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/16 14:34			0
2	BRS	L2	1	((aqueous and nonaqueous) with solvent) and 1	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/16 12:46			0
3	BRS	L3	8	(aqueous and nonaqueous) and 1	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/16 12:52			0
4	BRS	L4	258	((aqueous or water) with (alcohol or ketone or ester)) and 1	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/16 12:53			0
5	BRS	L5	97	4 and @pd<=20010830	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/16 14:35			0
6	BRS	L6	66	4 and @pd<=20000830	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/16 14:36			0
7	BRS	L7	0	(cmp or "chemical mechanical polishing") and "non aqueous"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/16 17:50			0
8	BRS	L8	253	(cmp or "chemical mechanical polishing") and "non aqueous"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/16 17:45			0

	Type	L #	Hits	Search Text	DBs	Time Stamp	C o m m e n t s	E r r o r s	E r r o r s
9	BRS	L9	69	8 and @pd<=20010830	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/16 16:47			0
10	BRS	L10	48	8 and @pd<=20000830	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/16 15:18			0
11	BRS	L11	83	((aqueous with slurry) with (alcohol or ketone or ester or organic)) and "chemical mechanical polishing"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/16 16:01			0
12	BRS	L12	13	((aqueous with slurry) with (organic with (medium or media))) and "chemical mechanical polishing"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/16 16:08			0
13	BRS	L13	0	((aqueous with slurry) with (nonaqueous with (medium or media))) and "chemical mechanical polishing"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/16 16:46			0
14	BRS	L14	19	(nonaqueous with (medium or media or solvent)) and "chemical mechanical polishing"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/16 16:47			0
15	BRS	L15	6	14 and @pd<=20010830	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/16 16:47			0
16	BRS	L18	0	(cmp or "chemical mechanical polishing") and (aniline or propanaliamide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/16 17:50			0